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Investigations on welding of fused silica using ultrafast double-pulse irradiation Sizhu Wu¹, Dong Wu¹, Jian Xu², Koji Sugioka^{1, 2}, Katsumi Midorikawa¹ ¹理化学研究所 緑川レーザー物理工学研究室 ²理化学研究所 理研-SIOM 連携研究ユニット

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Glass microwelding induced by an ultrafast laser has been drawing attention for applications such as optics, microelectromechanical systems, precision machinery, healthcare, and small satellites. Fused silica is a promising material for those applications due to its excellent electrical, chemical and especially optical properties. Recently, many groups have successfully demonstrated microwelding of fused silica using the ultrafast laser [1-2]. Meanwhile, we demonstrated for the first time that double-pulse irradiation of ultrafast laser pulses realized high efficiency microwelding of photostructurable glass [3]. The physical mechanism of glass microwelding by double-pulse irradiation has been further systematically investigated [4-5]. In this paper, we apply the ultrafast double-pulse irradiation technique for the fused silica microwelding.

The experimental setup is the same as that used for Foturanglass microwelding in previous studies [4-5]. Because of high melting point of fused silica, here we use an amplified femtosecond Er-fiber laser system (IMRA model FCPA μ Jewel D-1000) generates 457-fs pulses at a wavelength of 1045 nm with a repetition rate of 100 kHz. The substrates used were a commercially high-quality fused silica (Suprasil-P700). Figure 1 shows the optical microscope image of cross sections modified at different delay times with a pulse energy of 3.8 μ J. Figure 2 shows dependence of the modified depth on the delay time for three different pulse energies. We can see the delay time significantly affected the depth. The deepest depth of ~180.7 μ m was obtained at the delay time of 0.5 ps and a pulse energy of 3.8 μ J. The depth drastically decreases beyond 5 ps and is almost saturated after 100 ps.



 Fig.1 The optical microscope image of the depth
 Fig.2 The depth as function of delay time

 [1] T. Tamaki, et al., Jpn. J. Appl. Phys., 44, L687 (2005). [2] D. Helie, et al., Appl. Opt., 51,

 2098 (2012). [3] K. Sugioka, et al., Opt. Lett., 36, 2734 (2011). [4] S. Wu, et al., Opt. Express, 20,

 28893 (2012). [5] S. Wu, et al., Opt. Express, 21, 24049 (2013).